

Title (en)

METAL MASK MATERIAL AND PRODUCTION METHOD THEREFOR

Title (de)

METALLMASKENMATERIAL UND HERSTELLUNGSVERFAHREN DAFÜR

Title (fr)

MATÉRIAU POUR MASQUE MÉTALLIQUE, ET PROCÉDÉ DE FABRICATION DE CELUI-CI

Publication

EP 3508604 B1 20201209 (EN)

Application

EP 17846645 A 20170831

Priority

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- JP 2017031348 W 20170831

Abstract (en)

[origin: EP3508604A1] Provided are: a metal mask material the shape change of which after etching is suppressed and which has more excellent etching properties; and a production method for the metal mask material. The metal mask material has a surface roughness in the rolling direction and a surface roughness in a direction perpendicular to the rolling direction, which satisfy $0.05\text{ }\mu\text{m}\leq\text{Ra}\leq 0.25\text{ }\mu\text{m}$ and $\text{Rz}\leq 1.5\text{ }\mu\text{m}$, and has a skewness Rsk of less than 0. When a sample having a length of 150 mm and a width of 30 mm is cut out of the metal mask material and the thickness of the sample is reduced by 60% by etching from one side of the sample, the amount of warpage of the sample is 15 mm or less. The metal mask material has a thickness of not less than 0.01 mm but less than 0.10 mm.

IPC 8 full level

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CPC (source: EP KR)

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